

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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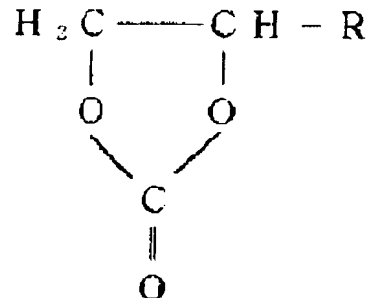
APPLICATION DATE : 10-07-92  
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APPLICANT : TOKYO OHKA KOGYO CO LTD;

INVENTOR : NAKAYAMA TOSHIMASA;

INT.CL. : G03F 7/32 H01L 21/027

TITLE : RINSE FOR LITHOGRAPHY AND  
PRODUCTION OF SEMICONDUCTOR  
DEVICE USING THE SAME



ABSTRACT : PURPOSE: To prevent the corrosion of a metallic circuit pattern by using a specific alkylene carbonate compound as a rinse.

CONSTITUTION: The rinse for lithography is composed of at least one kind of a compound selected from ethylene carbonate and propylene carbonate expressed by a formula or a mixture of at least one kind of a solvent selected from a water miscible organic solvent and water therewith and after removing a resist pattern on a substrate by an organic amine based releasing solution, the substrate is rinsed by the use of the rinse. In this case, the rinse contains alkylene carbonate, that is, ethylene carbonate, propylene carbonate or both of them as an essential component and these can be used individually or together. In the formula, R is hydrogen atom or methyl group.

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